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NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10057674	01/24/2002	430		1756	BARRECA, N

**APPLICANTS: Hwang Jeng; Mak Steve; Lin True-Lon; Ying Chentsau; Schaller John;

**CONTINUING DATA VERIFIED:

This application is a CON of 09/421,467 10/19/1999 ABN
 which is a CIP of 09/251,588 02/17/1999 ABN
 and is a CIP of 09/251,826 02/17/1999 PAT 6,323,132
 and is a CIP of 09/251,633 02/17/1999 PAT 6,265,318
 which is a CIP of 09/006,092 01/13/1998 ABN

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** FOREIGN APPLICATIONS VERIFIED: *none*

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed 35 USC 119 conditions met		<input type="checkbox"/> yes <i>no</i>	ATTORNEY DOCKET NO
Verified and Acknowledged Examiner's initials		<i>mb</i>	AM-2602.C1
TITLE : Masking methods and etching sequences for patterning electrodes of high density RAM capacitors			
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)			

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drwg.	Figs. Drwg.	Print Fig.
TERMINAL DISCLAIMER		Primary Examiner		
		PREPARED FOR ISSUE		
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